

Chemical Functionalization of Sc₃N@C₈₀

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Endohedral metallofullerenes have attracted special interest, because of the unique properties that are unexpected for empty fullerenes. Recently, the novel endohedral Sc₃N@C₈₀ has been prepared in remarkably high yield [1]. Sc₃N@C₈₀ contains a planar Sc₃N cluster confined within a C₈₀ cage with *I_h* symmetry. Sc₃N@C₈₀ can be formally described as a positively charged planer cluster of atoms inside a negatively charged icosahedral carbon cage, (Sc₃N)⁶⁺C₈₀⁶⁻ [1].

In our series of studies on the chemical functionalization of fullerenes with organosilicon compounds, we have reported the bis-silylation of fullerenes with disilirane [2]. In this context, it is worthy to note that disilirane can act as a mechanistic probe to clarify the electronic and chemical characteristics of fullerenes. Although Sc₃N@C₈₀ and La₂@C₈₀ have the same carbon cage with the same oxidation state (C₈₀(*I_h*)⁶⁻), LUMO level of Sc₃N@C₈₀ [3] is much higher than that of La₂@C₈₀ [4]. In this study, we report the redox property and the reactivity of Sc₃N@C₈₀ vs. La₂@C₈₀.

Thermal and photochemical reaction of Sc₃N@C₈₀ with 1,1,2,2-tetrakis(2,4,6-trimethylphenyl)-1,2-disilirane were performed (Scheme). Interestingly, photochemical reaction afforded mono-adducts, which structure determination was carried out by means of NMR measurement (Figure).

Scheme

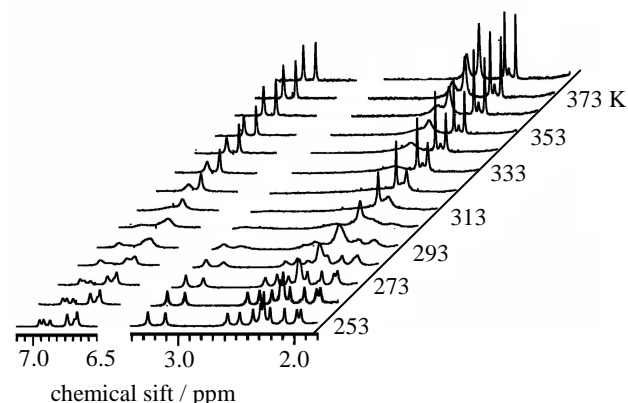
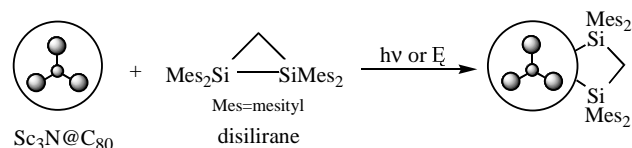


Figure. VT-¹H NMR spectra of mono-adducts

[1] Stevenson, S., *et al.*, *Nature* **1999**, 401, 55.

[2] For a review, see: Akasaka, T., *et al.*, *J. Synth. Org. Chem. Jpn.* **2000**, 58, 1066.

[3] Kobayashi, K., *et al.*, *J. Comput. Chem.* **2001**, 22, 1353.

[4] Kobayashi, K., *et al.*, *Chem. Phys. Lett.* **1995**, 245, 230.